



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

the application of:

Jinko KIMURA et al.

Serial No. 09/508,771

Filed: March 16, 2000

For: PHOTORESISTIVE FILM

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Atty. Docket No.: ASAMU0005
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Group Art Unit: 1752
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Examiner: C. Hamilton
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Date: March 27, 2001
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INFORMATION DISCLOSURE STATEMENT

Assistant Commissioner for Patents
Washington, D. C. 20231

Sir:

This is an Information Disclosure Statement with regard to the above-identified application.

Copies of each of the documents listed in the attached Form PTO/SB/08A are attached.

Document A relates to a photoresist cover film. Document B relates to propylene polymer composition. Document C relates to a propylene polymer film. Document D relates to an olefinic polymer. Document E relates to a polyester cover film. Document F relates to a photopolymerizable composition and layers. Document G relates to a photosensitive element, laminating method and resist forming method. Documents H, J and S relate to photosensitive resin compositions and films. Documents I, K, P, R, T and Y relate to photosensitive resin compositions and elements. Document L relates to a photosetting resin laminated body. Document M and N relate to photopolymerizable resin compositions. Document O relates to a photosetting resin composition. Document Q relates to a crosslink curable resin composition laminate. Document U relates to a photosensitive resin composition laminate, production of resist pattern, substrate, printed circuit board and apparatus. Documents V and W relate to photosensitive resin compositions and laminates. Document X relates to

